

Form PTO 1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT		ATTY DOCKET NO. 245959US2		SERIAL NO. NEW APPLICATION			
		APPLICANT Masakiyo MATSUMURA, et al.					
		FILING DATE HEREWITH		GROUP			
		U.S. PATENT DOCUMENTS					
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
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FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
	AO						
	AP						
	AQ						
	AR						
	AS						
	AT						
	AU						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
RK	AV	Masakiyo MATSUMURA, "Preparation of Ultra-Large Grain Silicon Thin-Films by Excimer-Laser", SURFACE SCIENCE, Vol. 21, No.5, March 2000, pp. 278-287					
RK	AW	M. NAKATA, et al., "Two-Dimensionally Position-Controlled Ultra-Large Grain Growth Based on Phase-Modulated Excimer-Laser Annealing Method", ELECTROCHEMICAL SOCIETY PROCEEDINGS, Vol. 2000-31, pgs. 148-153					
RK	AX	Mitsuru NAKATA, et al., "A New Nucleation-Site-Control Excimer-Laser-Crystallization Method", JAPANESE JOURNAL OF APPLIED PHYSICS, PART 1 REGULAR PAPERS, SHORT NOTES & REVIEW PAPERS, Vol. 40 No. 5A, May 2001, pgs. 3049-3054					
RK	AY	Chang-Ho OH, " Optimization of phase-modulated excimer-laser annealing method for growing highly-packed large-grains in Si thin-films, APPLIED SURFACE SCIENCE 154-155, 2000, pgs. 105-111					
RK	AZ	M. MATSUMURA, "Advanced Laser-Crystallization Technologies of Si for High-Performance TFTs, ALTEDEC, pgs. 263-266					
						<input type="checkbox"/> Additional References sheet(s) attached	
<i>/Robert Kunemund/</i>				Date Considered 06/12/2006			
Examiner							
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							